C.U.SHAH UNIVERSITY Summer Examination-2018

Subject Name : VLSI Technologies

	Subject Code : 4TE08VLS1		. S1	Branch: B.Tech (EEE)			
	Seme	ster: 8 Date	e : 01/05/2018	Time : 02:30 To 05:30	Marks : 70		
	 Instructions: (1) Use of Programmable calculator & any other electronic instrument is prohibited. (2) Instructions written on main answer book are strictly to be obeyed. (3) Draw neat diagrams and figures (if necessary) at right places. (4) Assume suitable data if needed. 						
Q-1	Attempt the following questions:						
	a)	Which of the mater A) Photoresistive	ials is used as gate? B) Polysilico	n C) Metal	D) Glass	01	
	b)	The of fabrication technique mechanical and enve A) Placement	of the VLSI chip ran tes for the packages rironmental protecti B) Floor-plan	nges from pre-assembly we sthat provide electrical co on. nning C) Packaging	vafer preparation to onnections and D) None	01	
	C)	A) Depletion mode	istor has conducting	B) Enhancemen D) Non- saturate	t mode	01	
	d)	If packing density a constraint, the techn A) BJT	rea and performand hology you prefer. B) CMOS	ce are the constraints, pow	D) PMOS	01	
	e)	The value of VGS t A) Pinch-off voltag	hat makes ID appro e B) Cutt-off vo	oximately zero is the ltage C) Ohmic	D) Breakdown voltage	01	
	f)	Using a hardware solution. A) Slower	olution for a digital B) Harder	system is always C) Easier	than a software D) Faster	01	
	g)	The final step in a device is called	lesign flow in which	h the logic design is imple	emented in the target	01	
	h)	A) Design entry is ideally	B) Simulation suited for application	C) Downloading ions using battery power of	g D) Compiling or battery backup power.	01	
		A) N-MOS	B) P-MOS	C) CMOS	D) MOS	01	

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i)	The time needed for an output to change as the result of an input change is known as				01
i)	A) Noise immunity	B) Fan-out	C) Rise time	D) Propagation delay	01
J <i>)</i>	A) Photoresist	B) N-channel	C) P-channel	D) None of these	01
k)	Which of the followin A) Accumulation mode C) Inversion mode on	ng is/are the operatin de only ly	g mode(s) of a MOS t B) Depletion mo D) All of the abo	ransistor? ode only ove	01
I)	 Which of the following is/are the region(s) A) Cut-off region only C) Non-saturated region only NMOS technology is preferred more than A) High switching speed C) Low cost of fabrication 		 (s) of operation of a MOS transistor? B) Saturated region only D) All of the above n PMOS technology due to B) Low power consumption D) None of these 		01 01
m)					
n)	In CMOS fabrication, A) True	nMOS and pMOS a	are integrated in same B) False	substrate.	01
Attempt Q-2	any four questions from Attempt all question	n Q-2 to Q-8 s			(14)
a)	Write a technical note	on MOSFET capac	itance.		07
b)	Explain the design hierarchy of VLSI technology.				07
Q-3	Attempt all question	S			(14)
a)) Write technical note on CMOS n-Well process.				07
b)	Explain VLSI Design flow using Y-chart.			07	
Q-4	Attempt all questions				(14)
a)	Explain briefly VLSI	design methodology	<i>.</i>		07
b)	Explain the constructi	on & working of a C	CMOS transistor.		07
Q-5	Attempt all question	s			(14)

a)	Explain the differences between NMos & PMos.	07
b)	Discuss CMOS SR latch circuits based on NOR2 gates.	07

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Q-6		Attempt all questions	
a)		Draw the circuit diagram of a CMOS edge-triggered D-latch and explain.	
	b)	Explain the differences between AOI and OAI.	07
Q-7		Attempt all questions	(14)
	a)	Give comparison between FPGA and CPLD.	07
	b)	Write a note on Built-In Self-Test (BIST).	07
Q-8		Attempt all questions	(14)
	a)	Explain CMOS dynamic circuit techniques.	07
	b)	Explain the basic principle of pass transistor circuit. Explain logic"1" transfer and logic "0" transfer.	07

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